

Electronic Supplementary Information

Remanufacturing transparent conductive oxide electrodes using ultrafast on-demand laser fabrication

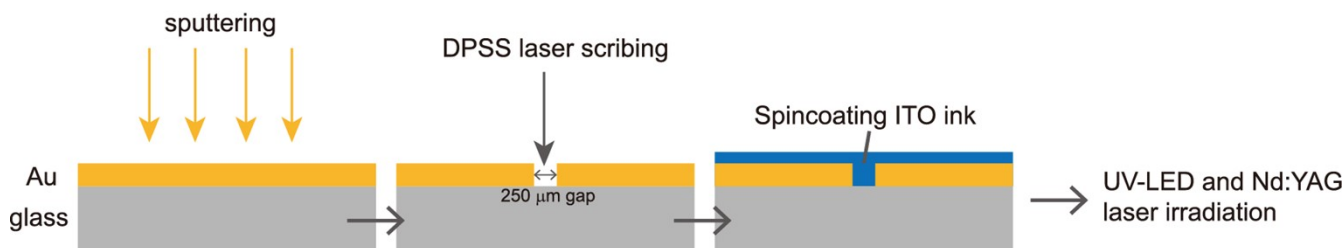
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Deposition methods of bottom electrodes before fabrications of ITO films

Two different methods of electrode formation were used for ITO film formation. For the test formation, a 250 μm wide gap was formed by laser scribing with a DPSS laser after sputtering Au formation. For the remanufacturing demonstration, ITO was formed by sputtering ITO through a metal mask to form a wiring defect pattern model.

For testing fab.



For remanufacturing demonstration

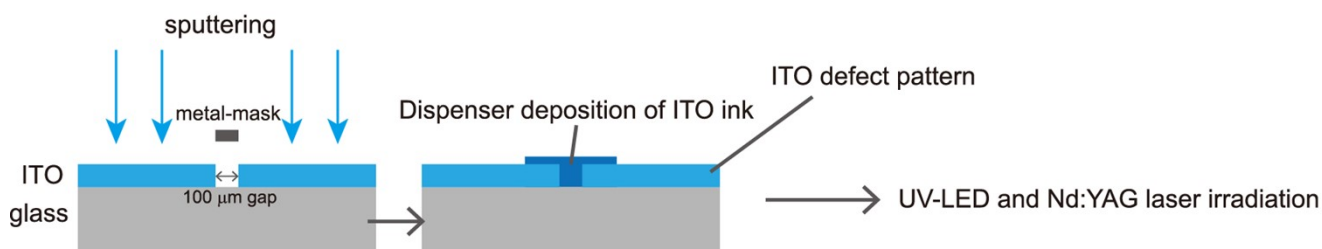


Fig. S1: Preparation procedures for testing fabrications and remanufacturing demonstration.